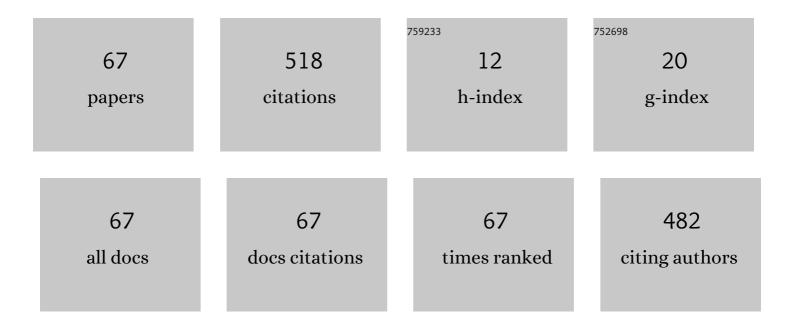
Denis V Marin

List of Publications by Year in descending order

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| # | Article | IF | CITATIONS |
|----|---|-----|-----------|
| 1 | Photodiodes based on p-on-n junctions formed in MBE-grown n-type MCT absorber layers for the spectral region 8 to 11Åμm. Infrared Physics and Technology, 2020, 105, 103182. | 2.9 | 8 |
| 2 | Direct comparison of the results of arsenic ion implantation in n– and p–type Hg0.8Cd0.2Te. Infrared Physics and Technology, 2020, 109, 103388. | 2.9 | 3 |
| 3 | Nano-size defects in arsenic-implanted HgCdTe films: a HRTEM study. Applied Nanoscience (Switzerland), 2019, 9, 725-730. | 3.1 | 12 |
| 4 | A Megapixel Matrix Photodetector of the Middle Infrared Range. Journal of Communications Technology and Electronics, 2019, 64, 1011-1015. | 0.5 | 5 |
| 5 | Effect of annealing on the structural properties of arsenic-implanted mercury cadmium telluride. Opto-electronics Review, 2019, 27, 14-17. | 2.4 | 2 |
| 6 | Ellipsometric Method for Measuring the CdTe Buffer-Layer Temperature in the Molecular-Beam Epitaxy of CdHgTe. Semiconductors, 2019, 53, 132-137. | 0.5 | 4 |
| 7 | Electrical profiling of arsenic-implanted HgCdTe films performed with discrete mobility spectrum analysis. Semiconductor Science and Technology, 2019, 34, 035009. | 2.0 | 10 |
| 8 | Photoluminescence of Molecular Beam Epitaxy-Grown Mercury Cadmium Telluride: Comparison of HgCdTe/GaAs and HgCdTe/Si Technologies. Journal of Electronic Materials, 2018, 47, 4731-4736. | 2.2 | 10 |
| 9 | Electrical properties of the Hg0.7Cd0.3Te films grown by MBE method on Si(0 1 3) substrates. Infrared Physics and Technology, 2018, 94, 11-15. | 2.9 | 5 |
| 10 | HgCdTe p ⁺ â€n structures grown by MBE on Si (013) substrates for high operating temperature SWIR detectors. Physica Status Solidi C: Current Topics in Solid State Physics, 2016, 13, 651-655. | 0.8 | 5 |
| 11 | Acceptor states in HgCdTe films grown by molecularâ€beam epitaxy on GaAs and Si substrates. Physica Status Solidi C: Current Topics in Solid State Physics, 2016, 13, 469-472. | 0.8 | 2 |
| 12 | CdHgTe heterostructures for new-generation IR photodetectors operating at elevated temperatures. Semiconductors, 2016, 50, 1626-1629. | 0.5 | 4 |
| 13 | Electrophysical properties of Cd x Hg1–x Te (x = 0.3) films grown by molecular beam epitaxy on Si(013) substrates. Physics of the Solid State, 2016, 58, 641-646. | 0.6 | 1 |
| 14 | Luminescence in GeO x films containing germanium nanoclusters. Nanotechnologies in Russia, 2016, 11, 325-330. | 0.7 | 3 |
| 15 | Methodological and instrumental problems in high-precision in situ ellipsometry diagnostics of the mercury cadmium telluride layer composition in molecular beam epitaxy. Instruments and Experimental Techniques, 2016, 59, 857-864. | 0.5 | 5 |
| 16 | The electrical properties of HgCdTe layers grown by MBE on Si and P + / n junction formed on its basis. , 2016, , . | | 2 |
| 17 | Electrical and optical studies of a telluriumâ€related defect in molecularâ€beam epitaxyâ€grown HgCdTe. Physica Status Solidi C: Current Topics in Solid State Physics, 2016, 13, 461-464. | 0.8 | 1 |
| 18 | High operating temperature SWIR p+–n FPA based on MBE-grown HgCdTe/Si(0 1 3). Infrared Physics and Technology, 2016, 76, 72-74. | 2.9 | 20 |

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| 19 | Defects in mercury-cadmium telluride heteroepitaxial structures grown by molecular-beam epitaxy on silicon substrates. Semiconductors, 2016, 50, 208-211. | 0.5 | 5 |
| 20 | Acceptor states and carrier lifetime in heteroepitaxial HgCdTe-on-Si for mid-infrared photodetectors. Journal of Physics: Conference Series, 2015, 643, 012004. | 0.4 | 3 |
| 21 | The reverse current temperature dependences of SWIR CdHgTe "p-on-n―and "n-on-p―junctions. Infrared Physics and Technology, 2015, 73, 312-315. | 2.9 | 16 |
| 22 | Applying an improved phonon confinement model to the analysis of Raman spectra of germanium nanocrystals. Journal of Experimental and Theoretical Physics, 2014, 118, 65-71. | 0.9 | 69 |
| 23 | Defects in heteroepitaxial CdHgTe/Si layers and their behavior under conditions of implanted p +-n photodiode structure formation. Technical Physics Letters, 2014, 40, 708-711. | 0.7 | 5 |
| 24 | Phase separation as a basis for the formation of light-emitting silicon nanoclusters in SiO x films irradiated with swift heavy ions. Optoelectronics, Instrumentation and Data Processing, 2014, 50, 292-297. | 0.6 | 1 |
| 25 | CdHgTe heterostructures on large-area Si(310) substrates for infrared photodetector arrays of the short-wavelength spectral range. Semiconductors, 2014, 48, 767-771. | 0.5 | 5 |
| 26 | Formation of Ge and GeSi nanocrystals in GeO _{<i>x</i>} /SiO ₂ multilayers. Journal Physics D: Applied Physics, 2013, 46, 275305. | 2.8 | 28 |
| 27 | Influence of irradiation with swift heavy ions on multilayer Si/SiO2 heterostructures. Semiconductors, 2013, 47, 358-364. | 0.5 | 3 |
| 28 | Light-emitting Si nanostructures formed by swift heavy ions in stoichiometric SiO2 layers. Nuclear Instruments & Methods in Physics Research B, 2012, 282, 68-72. | 1.4 | 9 |
| 29 | Anomalous temperature dependence of photoluminescence in GeO x films and GeO x /SiO2 nano-heterostructures. JETP Letters, 2012, 95, 424-428. | 1.4 | 9 |
| 30 | The effect of composition on the formation of light-emitting Si nanostructures in SiO x layers on irradiation with swift heavy ions. Semiconductors, 2011, 45, 408-414. | 0.5 | 2 |
| 31 | Formation of light-emitting nanostructures in layers of stoichiometric SiO2 irradiated with swift heavy ions. Semiconductors, 2011, 45, 1311-1316. | 0.5 | 3 |
| 32 | Light-emitting Si nanostructures formed in SiO2 on irradiation with swift heavy ions. Semiconductors, 2010, 44, 525-530. | 0.5 | 3 |
| 33 | Modification of germanium nanoclusters in GeO x films during isochronous furnace and pulse laser annealing. Technical Physics Letters, 2010, 36, 439-442. | 0.7 | 7 |
| 34 | Light-emitting Si nanostructures formed in silica layers byÂirradiation with swift heavy ions. Applied Physics A: Materials Science and Processing, 2010, 98, 873-877. | 2.3 | 8 |
| 35 | Anisotropic Strain – Anisotropic Heating Engineering for Silicon Nanocrystals in SiO ₂ . Solid State Phenomena, 2009, 156-158, 523-528. | 0.3 | 4 |
| 36 | Effect of pressure annealing on formation of lightâ€emitting Si nanocrystals in Si rich SiO ₂ . Physica Status Solidi (A) Applications and Materials Science, 2009, 206, 78-83. | 1.8 | 2 |

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|----|--|-----|-----------|
| 37 | Quasi-direct optical transitions in Ge nanocrystals embedded in GeO2 matrix. JETP Letters, 2009, 89, 76-79. | 1.4 | 4 |
| 38 | Ellipsometry of GeO2 films with Ge nanoclusters: Influence of the quantum-size effect on refractive index. Optics and Spectroscopy (English Translation of Optika I Spektroskopiya), 2009, 106, 436-440. | 0.6 | 6 |
| 39 | Structure and optical properties of SiN x : H films with Si nanoclusters produced by low-frequency plasma-enhanced chemical vapor deposition. Semiconductors, 2009, 43, 1514-1520. | 0.5 | 17 |
| 40 | The modification of Si nanocrystallites embedded in a dielectric matrix by high energy ion irradiation. Nanotechnology, 2009, 20, 095205. | 2.6 | 12 |
| 41 | The electrical properties of MOS-structures with silicon nanoballs incrusted in SiO <inf>2</inf> layer. , 2009, , . | | 0 |
| 42 | Photoinduced Variation of Capacitance Characteristics of MDS Structures with Three-Layer SiN _x Dielectrics. Solid State Phenomena, 2008, 131-133, 461-466. | 0.3 | 1 |
| 43 | Modification of Silicon Nanocrystals Embedded in an Oxide by High Energy Ion Implantation. Solid State Phenomena, 2008, 131-133, 541-546. | 0.3 | 3 |
| 44 | Structure and optical properties of silicon nanopowders. Materials Science and Engineering B: Solid-State Materials for Advanced Technology, 2008, 147, 222-225. | 3.5 | 20 |
| 45 | SiO x layer formation during plasma sputtering of Si and SiO2 targets. Semiconductors, 2008, 42, 731-736. | 0.5 | 11 |
| 46 | Effect of the ion-energy loss rate on defect formation during implantation in silicon nanocrystals. Semiconductors, 2008, 42, 1127-1131. | 0.5 | 3 |
| 47 | Formation of light-emitting Si nanostructures in SiO ₂ by pulsed anneals. Nanotechnology, 2008, 19, 355305. | 2.6 | 21 |
| 48 | High Volume Synthesis of Silicon Nanopowder by Electron Beam Ablation of Silicon Ingot at Atmospheric Pressure. Japanese Journal of Applied Physics, 2008, 47, 7019-7022. | 1.5 | 5 |
| 49 | <title>Falling down capacitance impedance under light illumination of MDS-structures with three-layer SiN<formula><inf><roman>x</roman></inf></formula> dielectrics</title> . Proceedings of SPIE, 2008, , . | 0.8 | 1 |
| 50 | <title>Ge nanoclusters in GeO<formula><inf><roman>2</roman></inf></formula>: formation and optical properties</title> . , 2006, 6260, 298. | | 1 |
| 51 | <title>Electronic transport through silicon nanocrystals embedded in SiO<formula><inf><roman>2</roman></inf></formula> matrix</title> . , 2006, , . | | 0 |
| 52 | Electrical properties and photoluminescence of SiOx layers with Si nanocrystals in relation to the SiOx composition. Semiconductors, 2006, 40, 1198-1203. | 0.5 | 17 |
| 53 | <title>Optical properties of silicon nanopowders formed using power electron beam evaporation</title> . , 2006, , . | | 1 |
| 54 | Modification of photoluminescence and charge in oxide with silicon nanocrystals by high energy ion implantation. , 2006, , . | | 0 |

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| 55 | The formation of silicon nanocrystals in SiO2 layers by the implantation of Si ions with intermediate heat treatments. Semiconductors, 2005, 39, 552-556. | 0.5 | 12 |
| 56 | Coulomb blockade of the conductivity of SiOx films due to one-electron charging of a silicon quantum dot in a chain of electronic states. Semiconductors, 2005, 39, 910-916. | 0.5 | 6 |
| 57 | Effect of Quantum Confinement on Optical Properties of Ge Nanocrystals in GeO[sub 2] Films. Semiconductors, 2005, 39, 1168. | 0.5 | 51 |
| 58 | Ge Nanoclusters in GeO ₂ : Synthesis and Optical Properties. Solid State Phenomena, 2005, 108-109, 83-90. | 0.3 | 3 |
| 59 | Laser Assisted Formation on Nanocrystals in Plasma-Chemical Deposited SiN _x Films. Solid State Phenomena, 2005, 108-109, 53-58. | 0.3 | 3 |
| 60 | Blue Photoluminescence from Quantum Size Silicon Nanopowder. Solid State Phenomena, 2005, 108-109, 65-70. | 0.3 | 1 |
| 61 | Laser Crystallization of Thin a-Si Films on Plastic Substrates Using Excimer Laser Treatments. Solid State Phenomena, 2004, 95-96, 29-34. | 0.3 | Ο |
| 62 | Visible photoluminescence from silicon nanopowders produced by silicon evaporation in a high-power electron beam. JETP Letters, 2004, 80, 544-547. | 1.4 | 14 |
| 63 | Structure and photoluminescence study of type-II GaAs quantum wires and dots grown on nano-faceted (311)A surface. Physica E: Low-Dimensional Systems and Nanostructures, 2004, 23, 461-465. | 2.7 | 3 |
| 64 | Ge quantum dots in anomalous thick native germanium oxide layers. , 2004, , . | | 0 |
| 65 | Photoluminescence of GeO2 films containing germanium nanocrystals. JETP Letters, 2003, 77, 411-414. | 1.4 | 15 |
| 66 | Nanocrystalline silicon films formed under the impact of pulsed excimer laser radiation on polyimide substrates. Technical Physics Letters, 2003, 29, 569-571. | 0.7 | 1 |
| 67 | Coulomb Blockade in Silicon Nanocrystals Embedded in SiO ₂ Matrix. Solid State Phenomena, 2003, 95-96, 629-634. | 0.3 | 2 |